ISC Audits & Reviews SC Summary (August 19, 2019)

Doc.	Title	Vote
5834-LI1;	Adding some explanations to 10.1.7;	Passed
5834-LI2;	Adding some explanation to NOTE 4;	Passed
5834-LI3;	Changing some words in 12.3.1;	Passed
5834-LI4;	Changing some words in 12.3.2;	Passed
5969A-LI1;	Addition of criteria to determine which method of assessing fire risk is to be used;	Passed
5969A-LI2;	Addition of use of the S10 ranking tables in place of the S14 ranking tables;	Passed
6049B-LI1;	Changes to Appendix 1: Changes pertaining to Severity Groups: People ;	Passed
6049B-LI4;	Changes to Appendix 1: Changes pertaining to Likelihood Groups;	Passed
6085A;	Revision to SEMI F57- 0314, Specification For Polymer Materials And Components Used In Ultrapure Water And Liquid Chemical Distribution Systems, with title change to: Specification For High Purity Polymer Materials And Components Used In Ultrapure Water And Liquid Chemical Distribution Systems ;	Passed
6175B;	New Standard: Guide on Measurements of Openings and Vias in Glass;	Passed
6236-LI1;	SEMI E172 - Correct editorial mistakes found in the E172 complementary file	Passed
6300C;	New Standard: Guide for EDA Freeze Version;	Passed
6311A;	New Standard: Specification for TEM Lamella Carrier Used in Electron Microscopy Workflows;	Passed
6348B;	Revision to E30-0418: Specification for the Generic Model for Communications and Control of Manufacturing Equipment (GEM);	Passed
6377B-LI1;	Make the following revisions to SECS message definitions in SEMI E5 to be compatible with SEMI E170-0419 and E170.1-0419. ;	Passed
6440;	Revision of SEMI M71-0912 Specification for Silicon-on-Insulator (SOI) Wafers for CMOS LSI;	Passed
6461;	Reapproval of SEMI M73-1013E Test Method for Extracting Relevant Characteristics from Measured Wafer Edge Profiles;	Passed
6470-LI1;	SEMI E5 - Multi-Block Inquire Clarification ;	Passed
6471-LI3;	SEMI T23 - Clarify device ID requirements ;	Passed
6471-LI4;	SEMI T23 - Update Device Traceability Across the Supply Chain Graphic ;	Passed
6472;	New Standard: Test Method for Measuring Surface Metal Contamination Through ICP-MS of Critical Chamber Components Used in Semiconductor Wafer Processing;	Passed
6478-LI1;	Unify expressions ‘Line Number’ and ‘LineID’, ‘Track Number’ and ‘TrackID’.;	Passed
6478-LI2;	Change EquipID from BYTE to WORD.;	Passed
6478-LI3;	Improve NetConfig and RouteConfig parameters.;	Passed

Doc.	Title	Vote
6478-LI4;	Specify Material Handoff Scenarios to be implemented.;	Passed
6478-LI5;	Change execution and propagation timing of SetRouteSpec.;	Passed
6478-LI6;	Add TOP/BOTTOM to SetRouteSpec message.;	Passed
6478-LI7;	Fill unused bytes of parameters with NULL.;	Passed
6478-LI8;	Add suggested signal conversion and conveyor width adjustment to Related Information 1.;	Passed
6481A-LI1;	Eliminate PEMFlag in response to the deletion of PEMFlag from E170 SFORMS;	Passed
6488;	New Standard: Guide for Chemical Mechanical Planarization (CMP) Particle Size Distribution (PSD) Measurement and Reporting used in Semiconductor Manufacturing;	Passed
6501;	Reapproval of SEMI M35-1114 Guide for Developing Specifications for Silicon Wafer Surface Features Detected by Automated Inspection;	Passed
6508;	Reapproval to SEMI E43-0813: Guide for Electrostatic Measurements on Objects and Surfaces;	Passed
6514;	Revision to SEMI A1-0519 Specification for Horizontal Communication (HC) Between Equipment for Factory Automation System and A1.1-0918 Specification for Media Interface for a Horizontal Communication (HC) Between Equipment;	Passed
6519;	Revision of SEMI M53-0219, Practice for Calibrating Scanning Surface Inspection Systems Using Certified Depositions of Monodispere Reference Spheres on Unpatterned Semiconductor Wafer Surfaces;	Passed
6528;	Reapproval to SEMI C51-0114, Specification for Xylenes;	Passed
6529;	Reapproval to SEMI C85-0214, Guide for Methyl Isobutyl Carbinol (MIBC);	Passed
6530;	Reapproval to SEMI C19-0514, Specification for Acetone;	Passed
6531;	Reapproval to SEMI C84-0214, Guide for Cyclopentanone;	Passed
R6192A;	Ratification Ballot - New Standard: Specification for Dry-Etched Patterned Sapphire Substrates (DPSS);	Passed
R6340C;	Ratification Ballot - Revision to SEMI F53-0600 (Reapproved 0412), Test Method for Evaluating the Electromagnetic Susceptibility of Thermal Mass Flow Controllers, with title change to Test Method for Evaluating the Electromagnetic Susceptibility of Mass Flow Controllers;	Passed
R6370;	Ratification Ballot - New Standard: Specification of Susceptors for HB-LED MOCVD Equipment Communication Interface;	Passed
M58-1109 (Reapproved 0614)	Test Method for Evaluating DMA Based Particle Deposition Systems and Processes [Editorial Changes]	Passed
M73-1013E	Test Method for Extracting Relevant Characteristics from Measured Wafer Edge Profiles [Editorial Changes]	Passed

Doc.	Title	Vote
S2-0818E	Environmental, Health, and Safety Guideline for Semiconductor Manufacturing Equipment [Editorial Changes for Miscellaneous]	Passed
S2-0818E	Environmental, Health, and Safety Guideline for Semiconductor Manufacturing Equipment [Editorial Changes for Trademarks Handling]	Passed

Line Item (LI)

For more information, please contact the SEMI Standards Engineer/Coordinator. (http://www.semi.org/standards/contacts) nearest you.

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